

d his

(FILE 'HOME' ENTERED AT 14:53:54 ON 24 APR 2006)

FILE 'REGISTRY' ENTERED AT 14:54:05 ON 24 APR 2006

L1 STR
L2 21 S L1
L3 STR L1
L4 3 S L3
L5 27 S L3 FUL

FILE 'CAPLUS' ENTERED AT 15:06:49 ON 24 APR 2006
L6 35 S L5

FILE 'REGISTRY' ENTERED AT 15:07:09 ON 24 APR 2006

FILE 'CAPLUS' ENTERED AT 15:15:13 ON 24 APR 2006

FILE 'STNGUIDE' ENTERED AT 15:27:14 ON 24 APR 2006

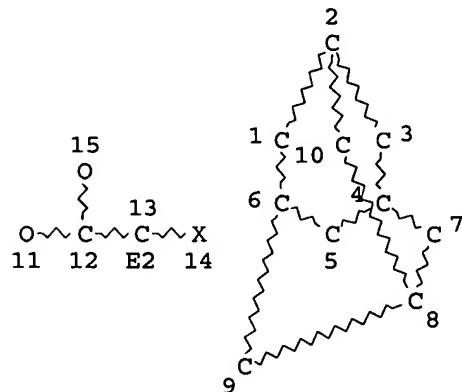
FILE 'CAPLUS' ENTERED AT 15:33:21 ON 24 APR 2006

FILE 'STNGUIDE' ENTERED AT 15:33:21 ON 24 APR 2006

=> d l3 sia

L3 HAS NO ANSWERS

L3 STR



NODE ATTRIBUTES:

HCOUNT IS E2 AT 13

DEFAULT MLEVEL IS ATOM

DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:

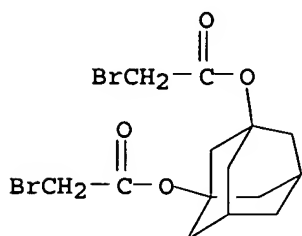
RSPEC I

NUMBER OF NODES IS 15

STEREO ATTRIBUTES: NONE

=>

L5 ANSWER 9 OF 27 REGISTRY COPYRIGHT 2006 ACS on STN
 RN 267423-13-2 REGISTRY
 ED Entered STN: 31 May 2000
 CN Acetic acid, bromo-, tricyclo[3.3.1.1^{3,7}]decane-1,3-diyl ester (9CI) (CA
 INDEX NAME)
 FS 3D CONCORD
 MF C14 H18 Br2 O4
 SR CA
 LC STN Files: CA, CAPLUS



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
 1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

REFERENCE 1

AN 132:341187 CA
 TI Contrast-boosted photoresist composition and fine patterning of the photoresist
 IN Namiki, Takahisa; Yano, Akira; Watabe, Keiji; Kon, Junichi
 PA Fujitsu Ltd., Japan
 SO Jpn. Kokai Tokkyo Koho, 9 pp.
 CODEN: JKXXAF
 DT Patent
 LA Japanese
 FAN.CNT 1

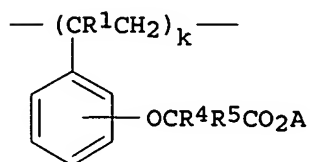
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2000131848	A2	20000512	JP 1999-142051	19990521
JP 1998-236108		19980821		

AB The composition contains a polymer and a compound substituted with OCOCR1R2X
 (X = halogen; R1, R2 = H, alkyl, Ph) for boosting contrast. The composition containing the polymer having side chain groups for reacting with acids to increase alkaline developer solubility, an agent for releasing acids under ionizing radiation, and the agent for boosting contrast is applied on a substrate to form a photoresist film, which is partially exposed, heated, and developed by an alkaline liquid to give the contrast-boosted pattern.

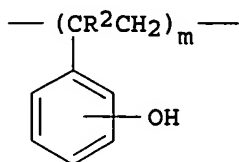
L6 ANSWER 25 OF 35 CAPLUS COPYRIGHT 2006 ACS on STN

1996:520454 Document No. 125:154399 Radiation-sensitive resist composition containing 1-adamantyl-substituted vinylphenol component. Matsuno, Shugo; Sugimoto, Tatsuya; Abe, Nobunori; Tanaka, Hideyuki (Nippon Zeon Co, Japan). Jpn. Kokai Tokkyo Koho JP 08137107 A2 19960531 Heisei, 7 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 1994-301558 19941110.

GI



I



II

AB The composition contains a copolymer having an adamantyl-substituted component I, a phenolic component II, and $[CR^3(CO_2R^6)]_n$ [$R^1-3 = H$, (substituted) $C1-4$ alkyl, halo, CN, NO_2 , R^4 , $R^5 = H$, (branched) $C1-8$ (substituted) alkyl, (substituted) alkenyl, (substituted) aryl, $A = 1$ -adamantyl, $R^6 =$ acid-instable group; $0.05 \leq k \leq 0.95$; $0.1 \leq l \leq 0.95$; $0.05 \leq n \leq 0.6$; $k + m + n = 1$] and a radiation-sensitive component which generates an acid by active radiation. The composition showing high sensitivity, resolution, and etching resistance is useful for super-fine processing in manufacture of semiconductor devices.

IT 180273-21-6DP, reaction products with hydroxy-containing acrylic polymers

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(radiation-sensitive resist composition containing 1-adamantyl-substituted vinylphenol component)

RN 180273-21-6 CAPLUS

CN Acetic acid, bromo-, tricyclo[3.3.1.1^{3,7}]dec-1-yl ester (9CI) (CA INDEX NAME)

